

ABSTRACT OF THE DISCLOSURE

A method of manufacturing a color wheel with filter sectors is disclosed. A resist film formed on a disk-like substrate of the color wheel is shaped into a mask pattern by photo processing, a metal mask which has openings configured similar to the filter sectors but having a slightly larger area than those is set on the substrate, and optical interference filters of a dielectric multi-layer film are formed by an evaporation method or a sputtering method, whereby the optical interference filters are formed so as to cover very limited portions of the mask pattern so that at lift-off process, resist remover can penetrate into the mask pattern from most portions of the mask pattern thus enabling the mask pattern to be removed easily and quickly.